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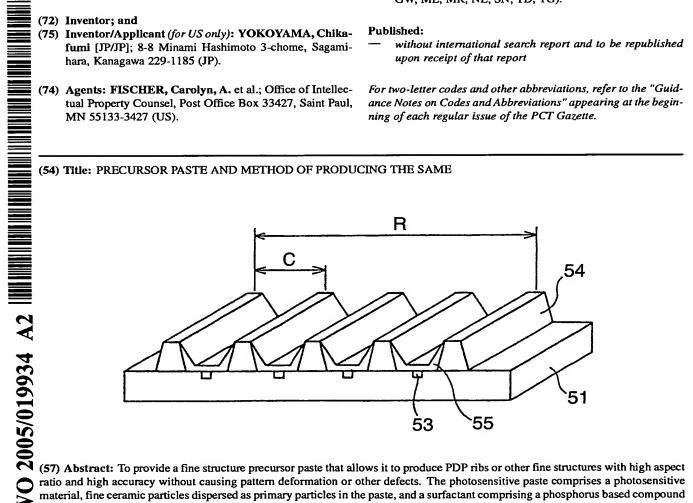
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ratio and high accuracy without causing pattern deformation or other defects. The photosensitive paste comprises a photosensitive material, fine ceramic particles dispersed as primary particles in the paste, and a surfactant comprising a phosphorus based compound and a sulfonate-based compound.